



NIP-154

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

M. IZAWA et al

Serial No. 09/373,723

Group Art Unit: 1763

Filed: August 13, 1999

Examiner: L. Alejandro Mulero

For: A DRY ETCHING METHOD

#8
7/24/01
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REPLY TO ELECTION REQUIREMENT

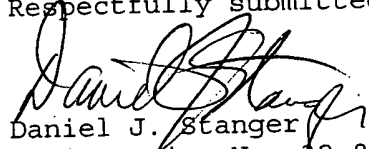
Commissioner for Patents
Washington, D.C. 20231

July 20, 2001

Sir:

In reply to the Office Action mailed June 21, 2001,
Applicants hereby elect the first embodiment directed to
performing an etching treatment which generates fluorine
radicals and CF₂ whereby the frequency of electromagnetic
waves used in the etching process is in a range from 300-600
MHz, on which claims 1-18 and 21 are readable.

Respectfully submitted,


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TC 1700 MAIL ROOM

JUL 24 2001

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Date: July 20, 2001